THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Chia-Lin Chen, et al.

Docket No.:

24061.42

Serial No.:

10/712,460

Examiner:

To Be Determined

Filed:

November 13, 2003

Art Unit:

1746

Entitled:

SEMICONDUCTOR WAFER

Conf. No.:

9316

MANUFACTURING METHODS

EMPLOYING CLEANING

DELAY PERIOD

INFORMATION DISCLOSURE STATEMENT

Commissioner For Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty of disclosure under 37 CFR §1.56, and in accordance with the practice under 37 CFR §1.97 and §1.98, the Examiner's attention is directed to the documents listed on the enclosed modified Form PTO-1449. No inference should be made that the cited references are in fact material, are in fact prior art, or that no better art exists. The cited patents are listed in numerical and alphabetical order and are not listed in any order based on their pertinence.

The above-identified application was filed after June 30, 2003. Therefore, pursuant to the waiver of the requirement under 37 CFR 1.98 (a)(2)(i) as stated in a Pre-OG Notice dated July 11, 2003, copies of the U.S. patents listed on the enclosed modified Form PTO-1449 are not being provided.

This Information Disclosure Statement is being filed within three months of the United States filing date or before the mailing date of a first Office Action on the merits. No certification or fee is required (37 CFR §1.97(b)).

The Commissioner is hereby authorized to charge any additional fees which may be required or credit any overpayment to Deposit Account 08-1394.

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Respectfully submitted,

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Timothy F. Bliss

Registration No. 50,925

Certificate of Mailing

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner For Patents, P.O. Box 1450, Alexandria, VA 22313date indicated below.

Date

Name

R-71720_1.DOC

Date: 4/12/04

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APR 1 5 2004

In place of PTO-1449 Form

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U. S. DEPARTMENT OF COMMERCE PATENT AND RADEMARK OFFICE TRADE

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

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Complete if Known				
Application Number 10/712,460				
Filing Date	November 13, 2003			
Applicant(s)	Chia-Lin Chen, et al.			
Art Unit	1746			
Examiner Name	To Be Determined			
Attorney Docket Number	24061.42 (TSMC2002-1015)			

U. S. PATENT DOCUMENTS					
Examiner's Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	
	AA	2002/0009900	01/24/02	Tay et al.	
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FOREIGN PATENT DOCUMENTS						
Examiner's Cite Foreign Patent Publication Date Patentee or Applicant of Cited Translation Initials No. Document Document (Country Code - Number - Kind)						

	OTHER PRIOR ART				
Examiner's	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article, title of the item, date, page(s), volume- issue number(s), publisher, city/country where published			
	AY	ARNUAD, F., ET AL., "Gate Oxide Process Impact on RNCE for Advanced CMOS Transistors", September 2002, ESSDERC '02, Firenze Italy, 21 pages.			
	AZ	LI, GENE, "Total Solutions for Front-End Thermal Processing", Foresight, May 2001, Pages 41-45.			
	ВА	ZONCA, R., ET AL., "Ultra Thin NO/N₂O Oxynitride Dielectric for Advanced Flash Memory Application: Single Wafer and Batch Technology", 6 pages.			
	BB	"Gate Stack", World Wide Web http://www.appliedmaterials.com/products/gate_stack.html, printed on February 17, 2003, 1 page.			
	ВС	"Technology Challenges for 100nn and Beyond Transistor and Capacitor Fabrication: Fig. 8", World Wide Web http://www.future-fab.com/assets/images/FFI11E1104F8.htm, printed on February 18, 2003, 1 page.			

Examiner		Date		
Signature		Consid	lered	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include a copy of this form with next communication to applicant.